



PATENT
Docket No. 29273/502

28812#
#10
R.R. Jones
2/23/2002

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT(S): Hajime KAWANO et al.
SERIAL NO. : 09/315,988
FILED : '21 May 1999
FOR : ELECTRON BEAM LITHOGRAPHY SYSTEM
ART UNIT : 2881
EXAMINER : K. Fernandez

ASSISTANT COMMISSIONER FOR
PATENTS AND TRADEMARKS
Washington, D.C. 20231

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TECHNOLOGY CENTER 2800

RESPONSE TO OFFICE ACTION

SIR:

Applicants submit the following remarks in response to the Office Action mailed August 14, 2001, the period for response having been extended herein to February 14, 2002 by payment of the requisite fee of \$920.00 for a Petition for Extension of Time Under 37 C.F.R. § 1.136(a):

REMARKS

Claims 1-4 have been rejected as anticipated by JP 63-001032. Applicants respectfully traverse this rejection. Although the reference is directed to forming patterns with a beam, it is completely different from the claimed arrangement.

The first claimed element is exposure map creating means. No such element is present in the reference. It has a pattern generator 10 in which patterns are pre-stored (see the description of Fig. 4).

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